

CLAIMS

67. (New) A physical vapor deposition target comprising a copper material with a face centered cubic unit cell, having a sputtering surface, and comprising:
- a predominate $\langle 220 \rangle$ crystallographic texture across the sputtering surface; and
 - an average grain size across the sputtering surface of less than or equal to about 30 microns.
68. (New) The physical vapor deposition target of claim 67 further comprising one or more of aluminum, silver, and gold.
69. (New) The physical vapor deposition target of claim 68 comprising aluminum.
70. (New) The physical vapor deposition target of claim 68 comprising silver.
71. (New) The physical vapor deposition target of claim 68 comprising gold.
72. (New) The physical vapor deposition target of claim 67 wherein the average grain size across the sputtering surface is less than or equal to 1 micron.
73. (New) The physical vapor deposition target of claim 67 further comprising substantially no pores or voids proximate the sputtering surface.

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74. (New) The physical vapor deposition target of claim 67 wherein the predominate <220> crystallographic texture is a strong <220> crystallographic texture.
75. (New) The physical vapor deposition target of claim 67 comprising a ratio of the <220> crystallographic orientation to all other orientations of the face centered cubic unit cell of at least about 80%.
76. (New) The physical vapor deposition target of claim 67 comprising a ratio of the <220> crystallographic orientation to all other orientations of the face centered cubic unit cell of at least about 90%.
77. (New) The physical vapor deposition target of claim 67 wherein substantially all of the grain sizes across the sputtering surface are less than about 30 microns.
78. (New) The physical vapor deposition target of claim 67 wherein substantially all of the grain sizes across the sputtering surface are less than 1 micron.
79. (New) The physical vapor deposition target of claim 67 wherein the <220> texture comprises predominately axial <220> orientations.
80. (New) The physical vapor deposition target of claim 67 wherein the <220> texture comprises predominately planar <220> orientations.

Appl. N . 09/705,101

81. (New) The physical vapor deposition target of claim 67 wherein any precipitates present in the target have a maximum dimension of 0.5 micron.

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